



Texiterra[®]
Natural oils for personal care

Skin Hydrating Cream



Formulation Ref: FM00323/A

A minimalistic skin cream which will help hydrate, soothe and protect your skin. Containing natural anti-oxidant **Texiterra BF Oryza**.

Phase	Ingredients	Function	% w/w	Supplier
A	Aqua	Solvent	Up to 100%	Ganesh Chemicals
	Sodium Benzoate and Potassium Benzoate	Preservative	0.50	
	Sodium Gluconate	Chelating Agent	0.10	
B	Acrylates/ C10 – 30 Alkyl Acrylates Cross Polymer	Rheology Modifier	0.60	Lubrizol
C	Cetyl Alcohol	Wax	2.00	S.D. Fine
	Caprylic/ Capric Triglyceride	Emollient	3.00	Naturganic
	Glyceryl Stearate (and) PEG-100 Stearate	Emulsifier	3.00	Croda
D	Bacillus / Rice Ferment Filtrate (and) Glycerin (and) Benzyl Alcohol (and) Lactic acid	Active	5.00	Texiterra BF Oryza (Scott Bader)
	Parfum	Fragrance (Snow Drop Fragrance)	0.50	Ultra International



Preparation procedure

1. Combine Phase A in main vessel and mix until completely dissolved.
2. Sprinkle in Phase B whilst homogenising. Homogenise until smooth and uniform. Start heating to 75 – 80°C.
3. In a separate vessel combine Phase C and heat to 75 - 80°C.
4. At temperature add Phase C into the main vessel and homogenise until smooth and uniform.
5. Cool to below 40°C with mixing.
6. At below 40°C add Phase D individually with mixing between additions. Mix until homogenous.

The information in this publication is based on laboratory testing and is believed to be accurate and is given in good faith, but no representation or warranty as to its completeness or accuracy is made. Suggestions for uses or applications are only opinions and are not intended for design purposes. Users are responsible for determining the suitability of these products for their own particular purpose and assume all risk and liability whether used singly or in combination with other materials. No representation or warranty, expressed or implied, is made with respect to information or products including, without limitation, warranties of merchantability, fitness for a particular purpose, non-infringement of any third party patent or other intellectual property rights.